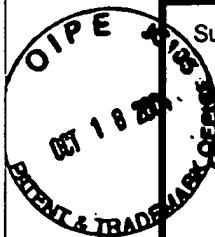


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		<b>Application Number</b>	09/905,718
		<b>Filing Date</b>	05/16/2001
		<b>First Named Inventor</b>	Willson et al.
		<b>Group Art Unit</b>	1762
		<b>Examiner Name</b>	Pianalto, Bernard D.
		<b>Attorney Docket Number</b>	PA27-02Q12
<b>Sheet</b>	1	of	1

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
THM	C1	Papirer et al., "The Grafting of Perfluorinated Silanes onto the Surface of Silica: Characterization by Inverse Gas Chromatography," August 1993, pp238-242, vol. 159, Issue 1.	
	C2	Abstract of Papirer et al., "The Grafting of Perfluorinated Silanes onto the Surface of Silica: Characterization by Inverse Gas Chromatography," August 1993, pp238-242, vol. 159, Issue 1.	
	C3	Hirai et al., "Mold Surface Treatment for Imprint Lithography," August 2001, pp 457-462, vol 14, No. 3.	
	C4	Abstract of Hirai et al., "Mold Surface Treatment for Imprint Lithography," August 2001, pp 457-462, vol 14, No. 3.	
	C5	Sung et al., "Micro/nano-tribological Characteristics of Self-Assembled Monolayer and its Application in Nano-Structure Fabrication," July 2003, pp. 808-818, vol. 255, no. 7.	
	C6	Abstract of Sung et al., "Micro/nano-tribological Characteristics of Self-Assembled Monolayer and its Application in Nano-Structure Fabrication," July 2003, pp. 808-818, vol. 255, no. 7.	
	C7	Roos et al., "Nanoimprint Lithography with a Commerical 4 Inch Bond System for Hot Embossing," October 2001, pp. 427-435, vol. 4343.	
THM	C8	Abstract of Roos et al., "Nanoimprint Lithography with a Commerical 4 Inch Bond System for Hot Embossing," October 2001, pp. 427-435, vol. 4343.	

Examiner Signature	Date Considered <span style="float: right;">12/15/04</span>
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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